

AMENDMENTS TO THE CLAIMS:

Please cancel claims 1-15 without prejudice to or disclaimer of the recited subject matter.

Please add new claims 16-28, as follows:

1-15. (Canceled)

16. (New) An exposure apparatus which has an optical system and transfers a pattern of a mask to a substrate via said optical system, said apparatus comprising:

a structure;

a partition wall which defines a space including an optical path of said optical system; and

an elastic seal member which couples said structure and said partition wall to seal the space,

wherein said elastic seal member is arranged so that a hollow cylinder is compressed in a direction of an axis of the hollow cylinder, the hollow cylinder in an uncompressed state being comprised of a member undulated in a cross section perpendicular to the axis and a shape of the uncompressed-state hollow cylinder in the cross section being substantially uniform along the axis.

17. (New) An apparatus according to claim 16, wherein a form of said elastic seal member in the cross section has a plurality of protrusions.

18. (New) An apparatus according to claim 16, wherein said elastic seal member is made of a material selected from the group consisting of resin and rubber.

19. (New) An apparatus according to claim 16, wherein said elastic seal member is made of fluororubber.

20. (New) An apparatus according to claim 16, wherein said elastic seal member has a thickness not greater than 2 mm.

21. (New) An apparatus according to claim 16, wherein said elastic seal member is resistant to a gage pressure of 1 MPa.

22. (New) An apparatus according to claim 16, wherein said elastic seal member is comprised of the undulated member arranged in a shape as the undulated member is arranged on side surfaces of a polygonal cylinder.

23. (New) An apparatus according to claim 16, wherein said elastic seal member is comprised of the undulated member arranged in a shape as the undulated member is arranged on side surfaces of a circular cylinder.

24. (New) An apparatus according to claim 16, wherein said structure is supported via a vibration isolating mechanism, and said partition wall is supported by a support member without a vibration isolating mechanism.

25. (New) An apparatus according to claim 16, wherein said apparatus comprises a plurality of said structures, and a plurality of said elastic seal members corresponding to said plurality of said structures, respectively.

26. (New) An apparatus according to claim 16, wherein said structure is supported by a support member without a vibration isolating mechanism, and said partition wall is supported via a vibration isolating mechanism.

27. (New) An apparatus according to claim 16, further comprising a stage to hold one of the mask and the substrate, wherein said stage is arranged in the space.

28. (New) A device manufacturing method comprising steps of:
transferring a pattern to a substrate using an exposure apparatus as defined in claim 16; and
developing the substrate to which the pattern has been transferred.